

COVER DEVICE, PROCESS CHAMBER AND SEMICONDUCTOR PROCESS APPARATUS

ABSTRACT

5

The present disclosure provides a cover device, a process chamber, and a semiconductor process apparatus. The provided cover device includes a cover, a connection base, and a cover base, a first end of the cover base is rotatably connected to the connection base, the cover base has a first state and a second state, and a
10 second end of the cover base is rotatable around the first end of the cover base to switch the cover base between the first state and the second state; in the first state of the cover base, the cover is tilted relative to a preset plane, and the cover is movable relative to the cover base; and in the second state of the cover base, the cover is parallel to the preset plane. The solution can solve the problem of poor sealing of a
15 process chamber in the related technology.

FIG 2